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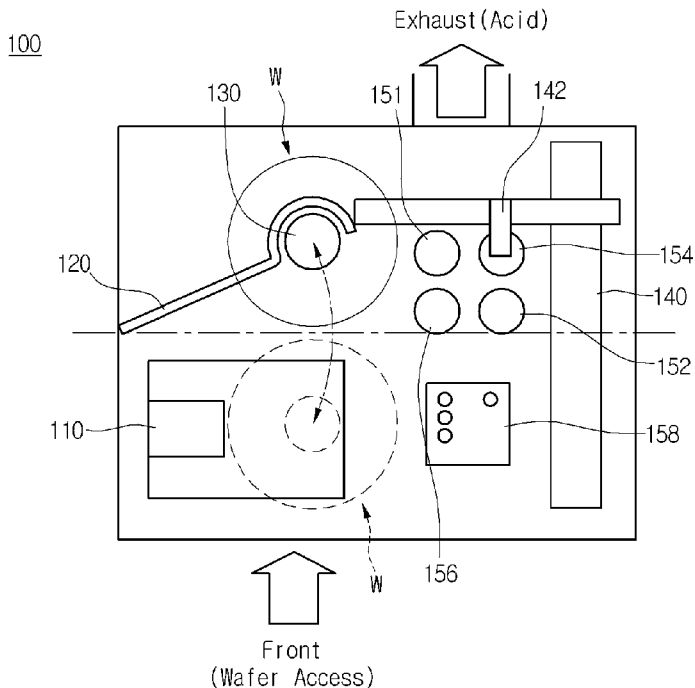
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(54) Title: APPARATUS FOR MEASURING IMPURITIES ON WAFER AND METHOD OF MEASURING IMPURITIES ON WAFER

[Fig. 1]



(57) Abstract: Provided are an apparatus for measuring impurities on a wafer and a method of measuring impurities on a wafer. The apparatus includes: a wafer aligning device for aligning a wafer; a loading robot for moving and loading the aligned wafer; a rotation stage for rotating the loaded wafer; a scan robot for holding a natural oxide layer etching solution for the wafer and a metallic impurity recovery solution; and a container for receiving a predetermined etching solution and a recovery solution, wherein the scan robot removes an oxide layer on an edge region of the wafer.

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**A. CLASSIFICATION OF SUBJECT MATTER****H01L 21/66(2006.01)i**

According to International Patent Classification (IPC) or to both national classification and IPC

**B. FIELDS SEARCHED**

Minimum documentation searched (classification system followed by classification symbols)

H01L 21/66; H01L 21/02

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Korean utility models and applications for utility models

Japanese utility models and applications for utility models

Electronic data base consulted during the international search (name of data base and, where practicable, search terms used)

eKOMPASS(KIPO internal) &amp; Keywords: impurit\*, measure\*, solution, wafer, substrate

**C. DOCUMENTS CONSIDERED TO BE RELEVANT**

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
Y	KR 10-2002-0074757 A (SAMSUNG ELECTRONCS CO., LTD.) 04 October 2002 See abstract; figures 1-7; page 2, line 44 - page 5, line 51	1-6, 11-12
Y	KR 10-2004-0001918 A (HYNIX SEMICONDUCTOR INC.) 07 January 2004 See abstract; figures 1-3; page 2 line 46- page 3 line 55	1-6, 11-12
A	KR 10-2004-0055934 A (SAMSUNG ELECTRONICS CO., LTD.) 30 June 2004 See abstract; figure 9; page 3, line 10 - page 7, line 44	1-12

 Further documents are listed in the continuation of Box C. See patent family annex.

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**INTERNATIONAL SEARCH REPORT**

Information on patent family members

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Patent document cited in search report	Publication date	Patent family member(s)	Publication date
KR 10-2002-0074757 A	04.10.2002	US 2002-0134406 A1 US 6960265 B2	26.09.2002 01.11.2005
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